

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant:	Gabric, <i>et al.</i>	Docket No.:	INF 2006 VJ 33543 US
Serial No.:	10/586,788	Art Unit:	2893
Filed:	September 2, 2008	Examiner:	Nikolay K. Yushin
		Conf. No.:	1598

For: Plasma Excited Chemical Vapor Deposition Method  
Silicon/Oxygen/Nitrogen-Containing-Material and Layered Assembly

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**AMENDMENT**

Dear Sir:

The following amendments and remarks are presented in response to the Examiner's Office Action mailed June 4, 2009. Please amend the above-referenced application as follows.